

ABSTRACT

5 A composition for etching of a ruthenium-based
metal, in which there are added and mixed at least a
bromine-containing compound, an oxidizing agent, a basic
10 compound and water, wherein the amount of bromine-
containing compound added is 2-25 mass%, as bromine, and
the amount of oxidizing agent added is 0.1-12 mass%, with
respect to the total mass, and the pH is at least 10 and
10 less than 12. It is possible to accomplish efficient
etching of ruthenium-based metals.